

WEST Search History

DATE: Friday, May 11, 2007

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<i>DB=PGPB,USPT; PLUR=YES; OP=ADJ</i>			
<input type="checkbox"/>	L2	clean\$ with lens with ((immersion lithography system) or ILS) and surfactant	2
<input type="checkbox"/>	L1	clean\$ with lens with ((immersion lithography system) or ILS) with surfactant	0

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Search Results - Record(s) 1 through 2 of 2 returned.

1. Document ID: US 20070091287 A1

L2: Entry 1 of 2

File: PGPB

Apr 26, 2007

PGPUB-DOCUMENT-NUMBER: 20070091287

PGPUB-FILING-TYPE:

DOCUMENT-IDENTIFIER: US 20070091287 A1

TITLE: IMMERSION LITHOGRAPHY APPARATUS AND METHODS

PUBLICATION-DATE: April 26, 2007

INVENTOR-INFORMATION:

NAME	CITY	STATE	COUNTRY
CHANG; Ching-Yu	Yilang County		TW
LIN; Burn Jeng	Hsin-Chu		TW
LIN; Chin-Hsiang	Hsin-Chu		TW

US-CL-CURRENT: 355/30; 355/53

ABSTRACT:

A lithography apparatus includes an imaging lens module; a substrate table positioned underlying the imaging lens module and configured to hold a substrate; and a cleaning module adapted to clean the lithography apparatus. The cleaning module is selected from the group consisting of an ultrasonic unit, a scrubber, a fluid jet, an electrostatic cleaner, and combinations thereof.

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2. Document ID: US 20050205108 A1

L2: Entry 2 of 2

File: PGPB

Sep 22, 2005

PGPUB-DOCUMENT-NUMBER: 20050205108

PGPUB-FILING-TYPE: new

DOCUMENT-IDENTIFIER: US 20050205108 A1

TITLE: Method and system for immersion lithography lens cleaning

PUBLICATION-DATE: September 22, 2005

INVENTOR-INFORMATION:

NAME	CITY	STATE	COUNTRY
Chang, Ching-Yu	Yen-Sun		TW
Lin, Chin-Hsiang	Hsin-Chu		TW

US-CL-CURRENT: 134/1; 355/53

ABSTRACT:

A method and system for cleaning lens used in an immersion lithography system is disclosed. After positioning a wafer in the immersion lithography system, a light exposing operation is performed on the wafer using an objective lens immersed in a first fluid containing surfactant, wherein the surfactant reduces a likelihood for having floating defects adhere to the wafer and the objective lens.

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Term	Documents
LENS	333915
LENSES	150203
IMMERSION	91658
IMMERSIONS	1268
LITHOGRAPHY	68840
LITHOGRAPHIES	353
LITHOGRAPHYS	1
SYSTEM	3086267
SYSTEMS	1901229
ILS	3491
IL	373646
(CLEAN\$ WITH LENS WITH ((IMMERSION LITHOGRAPHY SYSTEM) OR ILS) AND SURFACTANT).PGPB,USPT.	2

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